Docket No.: M4065.1006/P1006-B (PATENT)

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Terry L. Gilton

Application No.: 10/618,824

Group Art Unit: N/A

Filed: July 14, 2003

Examiner: Not Yet Assigned

For:

PROGRAMMABLE CONDUCTOR

MEMORY CELL STRUCTURE AND

METHOD THEREFOR

## INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents Washington, DC 20231

Dear Sir:

Pursuant to 37 C.F.R. § 1.56, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached PTO/SB/08. It is respectfully requested that the subject matter of the documents be expressly considered during the prosecution of this application and that the documents be made of record therein and appear among the "References Cited" on any patent to issue form this application. A copy of each document is attached.

Those patents and publications which are marked with an asterisk (\*) in the attached form PTO/SB/08 are not supplied because they were previously cited by or submitted to the Office in a prior application no. 10/121,790, filed April 10, 2002, and relied upon in this application for an earlier filing date under 35 U.S.C. 120.

A brief explanation of relevance of the non-U.S. patent documents listed on form PTO/SB/08 is provided and attached hereto as Appendix A. The brief explanation provided for each document is <u>not</u> tantamount to an admission that a document is

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"material" or that it qualifies as prior art. The Examiner is respectfully requested to utilize Appendix A only as a tool by which to better categorize the documents for substantive use in examining the claims of the application.

Documents discussed in Appendix A marked with an asterisk (\*\*) are indicated to be potentially more relevant than others. Such marking is provided only to assist the Examiner; however, the Examiner is requested to thoroughly review all documents cited herein.

In accordance with 37 C.F.R. § 1.97(g), the filing of this Information Disclosure Statement shall not be construed to mean that a search has been made or that no other material information as defined in 37 C.F.R. § 1.56(a) exists. It is submitted that the Information Disclosure Statement is in compliance with 37 C.F.R. § 1.98 and the Examiner is respectfully requested to consider and cite the listed documents.

The Commissioner is hereby authorized to charge any deficiency in the fees filed, asserted to be filed or which should have been filed herewith (or with any paper hereafter filed in this application by this firm) to our Deposit Account No. 04-1073, under Order No. M4065.1006/P1006-A. A duplicate copy of this paper is enclosed.

Dated: February 27, 2004

Respectfully submitted,

Thomas J. D'Amico

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Substitu	ute for form 1449A	VPTO		Complete if Known		
				Application Number	Not Yet Assigned	
	-		SCLOSURE	Filing Date	February 25, 2004	
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	NFORMATIO			Filing Date	February 25, 2004	
S	STATEMENT	BY A	APPLICANT	First Named Inventor	Terry L. Gilton	
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Initials* No.1		Country Code <sup>3</sup> -Number <sup>4</sup> -Kind Code <sup>5</sup> (if known)	MM-DD-YYYY	Applicant of Cited Document	Passages or Relevant Figures Appear	76
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<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant

<sup>&</sup>lt;sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> See attached Kinds Codes of USPTO Patent Documents at <a href="www.uspto.gov">www.uspto.gov</a> or MPEP 901.04. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the application number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup> Applicant is to place a check mark here if English language Translation is attached.

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				Group Art Unit	N/A
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9	STATEMENT	BY A	APPLICANT	First Named Inventor	Terry L. Gilton	
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Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number. Complete if Known Substitute for form 1449B/PTO Application Number 10/618,824 INFORMATION DISCLOSURE July 14, 2003 Filing Date STATEMENT BY APPLICANT Terry L. Gilton First Named Inventor N/A Group Art Unit (use as many sheets as necessary) Examiner Name Not Yet Assigned of 12 M4065 1006/P1006-B

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